Search Notes

_	Application No.	Applicant(s)
	10/630,716	FUKUYAMA ET AL.
	Examiner	Art Unit
	Stephen W. Smoot	2813

	SEARCHED				
Class	Subclass	Date	Examiner		
438	623	8/20/2004	sws		
438	624	6/20/2004	sws		
438	637	6/20/2004	sws		
438	638	6/20/2004	sws		
438	675	8/20/2004	sws		
438	763	8/20/2004	sws	000.0	
438	780	8/20/2004	sws	}&W.&	
257	635	8/20/2004	sws] [
257	637 ′	8/20/2004	sws		
257	642	8/20/2004	sws		
257	774	8/20/2004	sws		
257	775	8/20/2004	sws		
257	E23.145	8/20/2004	sws /		
Updated	Above	2/3/2005		g.W.L.	
Updated Above 5-16-05 SiNA,				1	
INT					
Class	Subclass	Date	Examiner	-	

5/16/2005

	SEARCH NOTES (INCLUDING SEARCH STRATEGY)				
		DATE	EXMR		
	Key Words: Low Dielectric Constant - Low k, Low Permittivity; Contact Hole, Opening Via; Interconnect - Trace, Line, Wiring;	8/20/2004	LW,Q, sws		
	Interlayer, ILD, IMD - Organic, Porous Silica; Borderless Contact; Transistor - Source, Gate, Drain.	8/20/2004	SWS,		
)	Updated Above Search	2/3/2005	INQ, sws		
	Updated Above Search	5/16/2005	IN.J. sws		
	Search Tools - EAST (attached): USPAT; US PG PUBS; Derwent; EPO; JPO; IBM TDB	8/20/2004; 2-3-05; 8/ 5-16-05	sws 		

Same as Above